

Chemical Vapor Deposition of Uranium Ditelluride (UTe_2)

By: Kimia Samieinejad

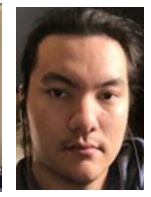
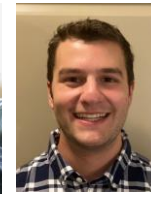
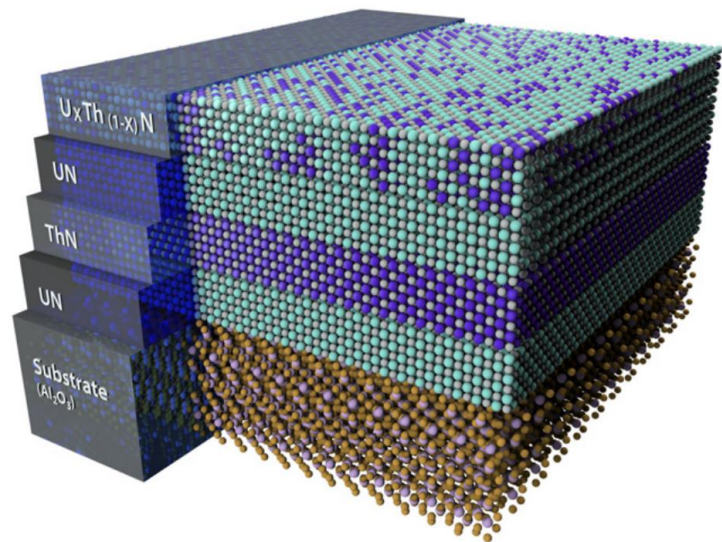


Outline:

- Goal
- Background
- Chemical Vapor Deposition of UTe₂
 - Software Simulation
 - Experimental Setup
- Future Work
- Summary

What is our goal?

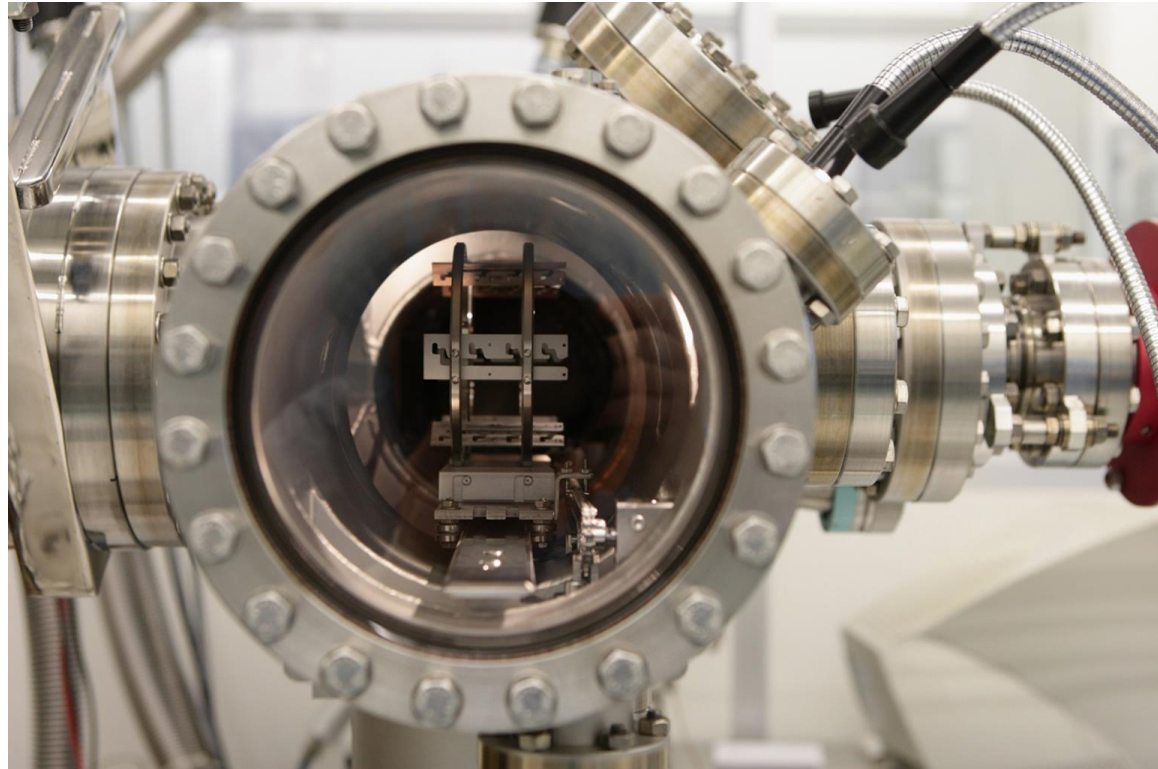
Grow thin films of actinides particularly UTe₂



Citation Kevin D Vallejo *et al* 2022 *Rep. Prog. Phys.* 85 123101
DOI 10.1088/1361-6633/ac968e

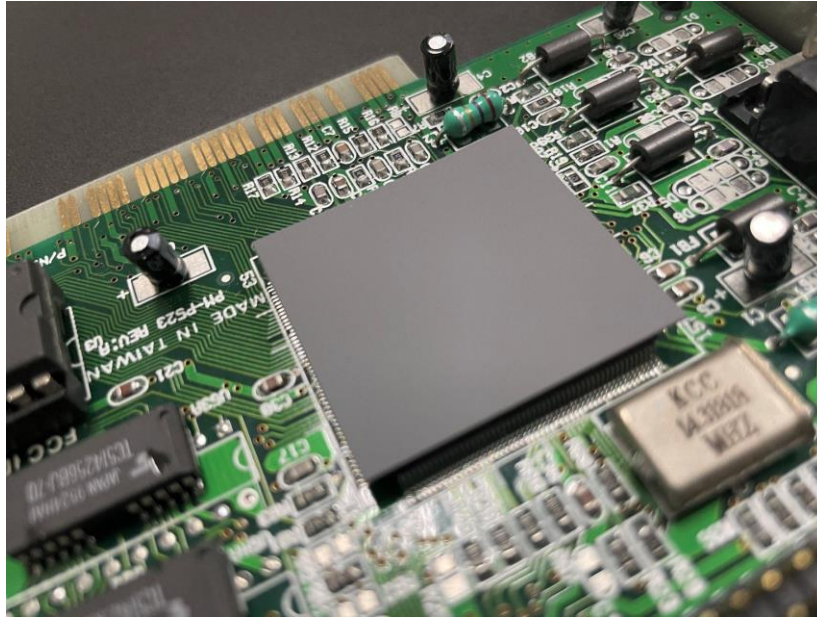
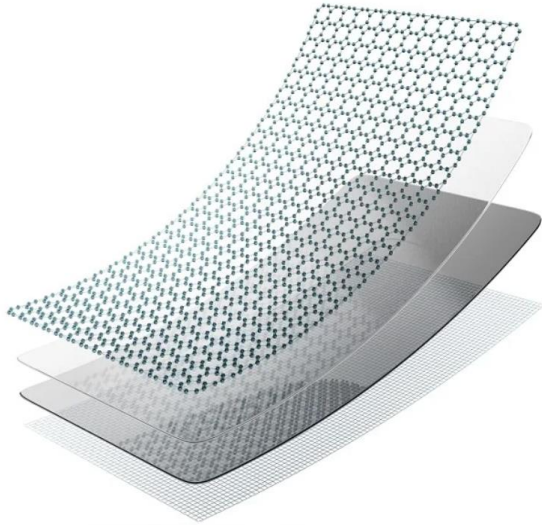
Why?

- Thin Films?
- UTe_2 ?
- Chemical Vapor Deposition?



Thin Films Deposition
<https://www.micronit.com/manufacturing/capabilities/thin-film-deposition>

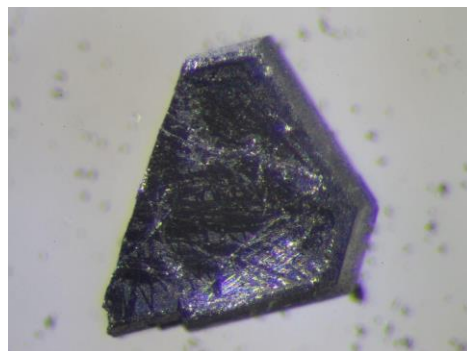
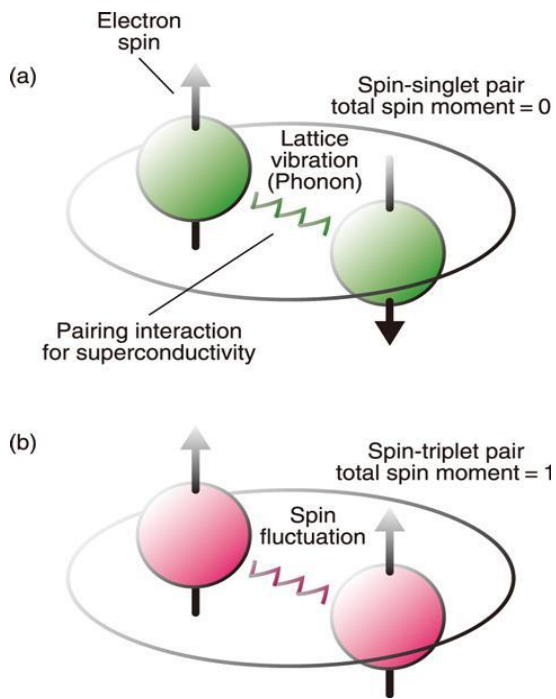
Thin Films (10^{-9} m)



*Image Credit: Laremenko
Sergii/Shutterstock.com*

<https://streuter.com/timtel-thermal-interface-materials/sitel-thermal-interface-silicone-film-materials-electronics-cooling/>

UTe₂, a spin triplet superconductor



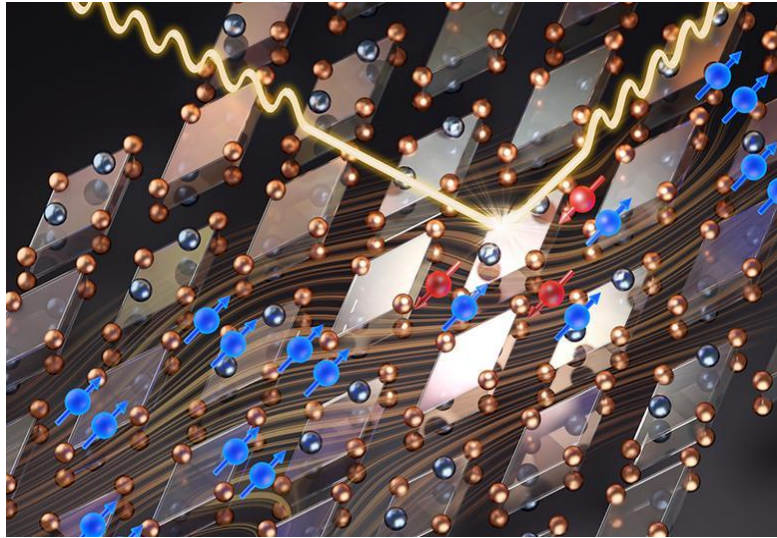
UTe₂ (CVT, Corey Frank)



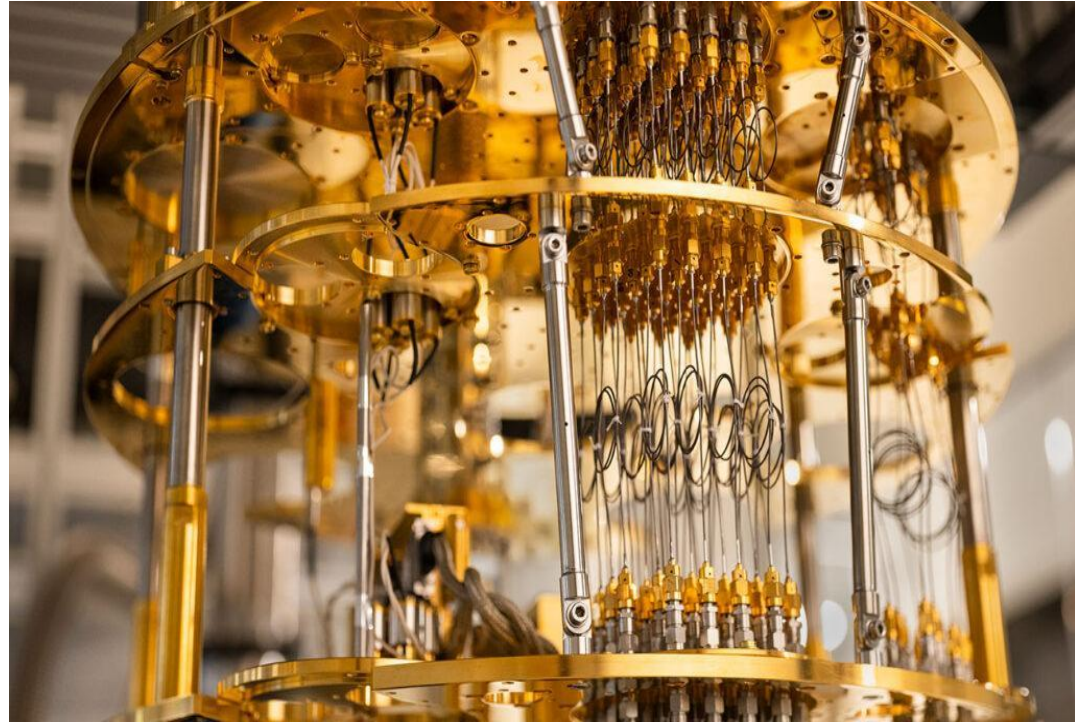
Image Credit: F. Webber/NIST

Two types of superconducting electron pairs
https://rdreview.jaea.go.jp/review_en/2020/e2020_3_3.html

UTe₂ and Quantum Computers?!

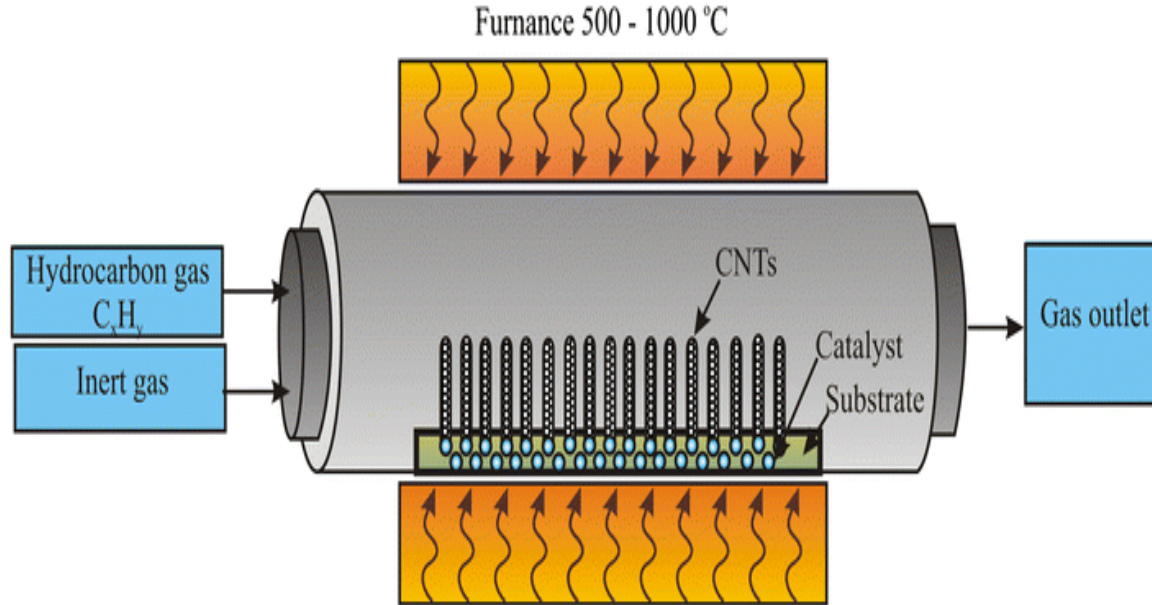


(Credit: Jill Hemman/ORNL)w54657r43www



<https://www.microsoft.com/en-us/research/blog/microsoft-has-demonstrated-the-underlying-physics-required-to-create-a-new-kind-of-qubit/>

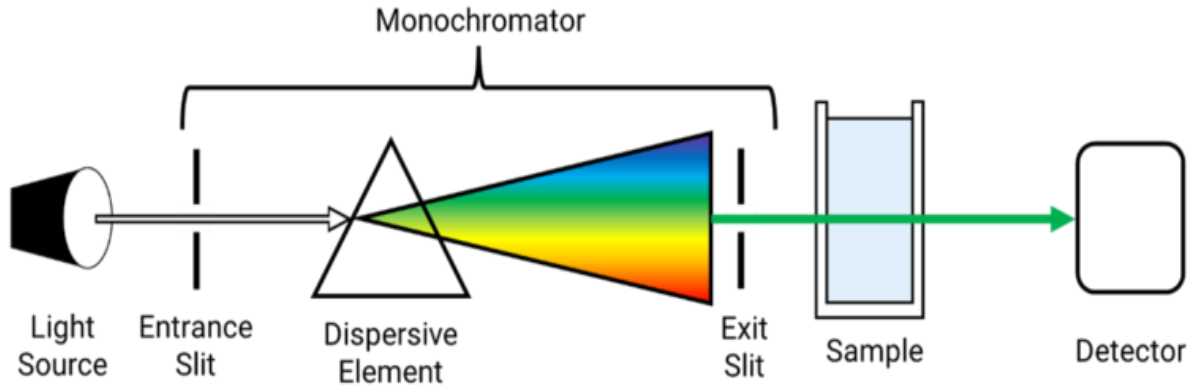
What exactly is Chemical Vapor Deposition?



CNT: Carbon
Nanotubes

What are we going to do differently in our experiments compared to others?

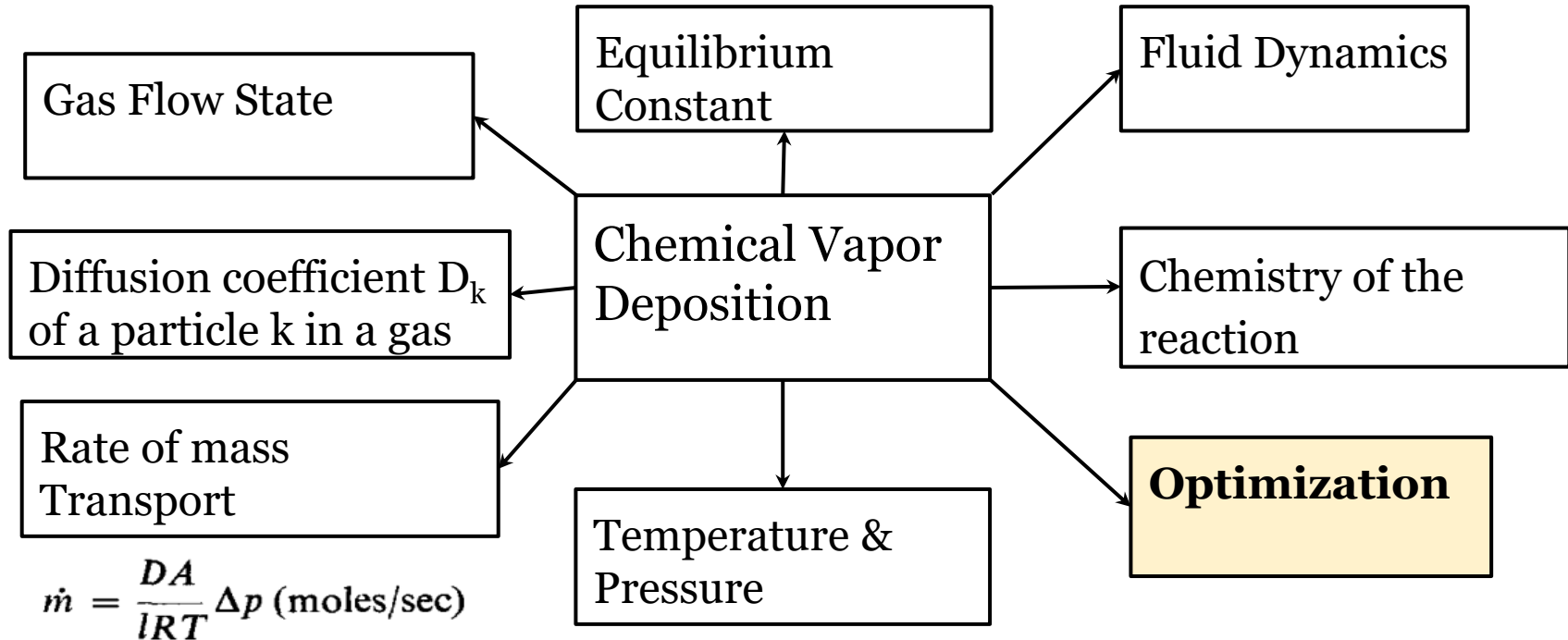
- Monitor and control the reaction on real-time

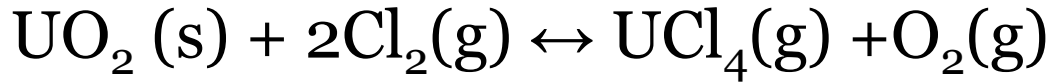


A basic block diagram of the elements in a single beam UV-Visible spectrometer
<https://jascoinc.com/learning-center/theory/spectroscopy/uv-vis-spectroscopy/instrumentation/>

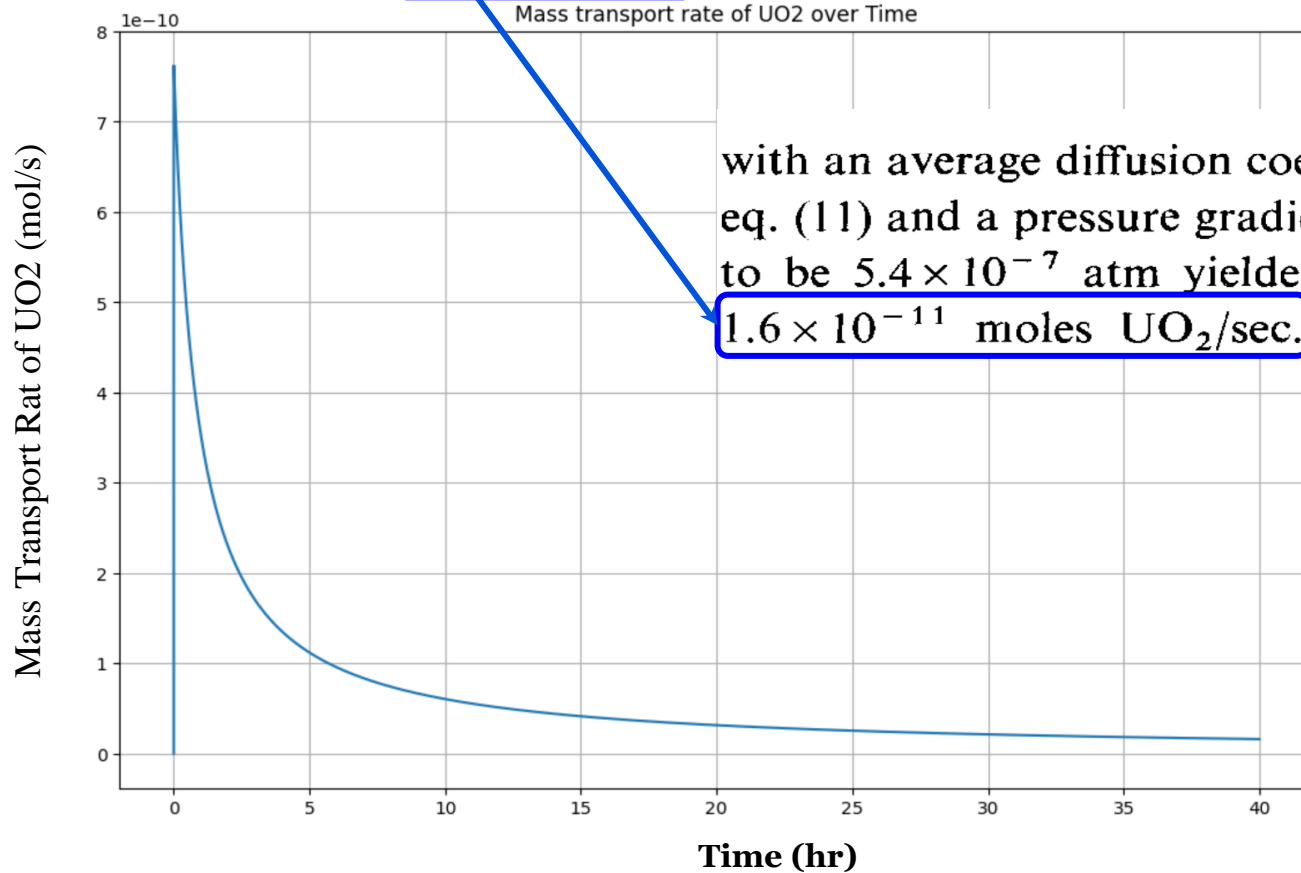
Developing a Simulation Software

Why do we need a simulation software?





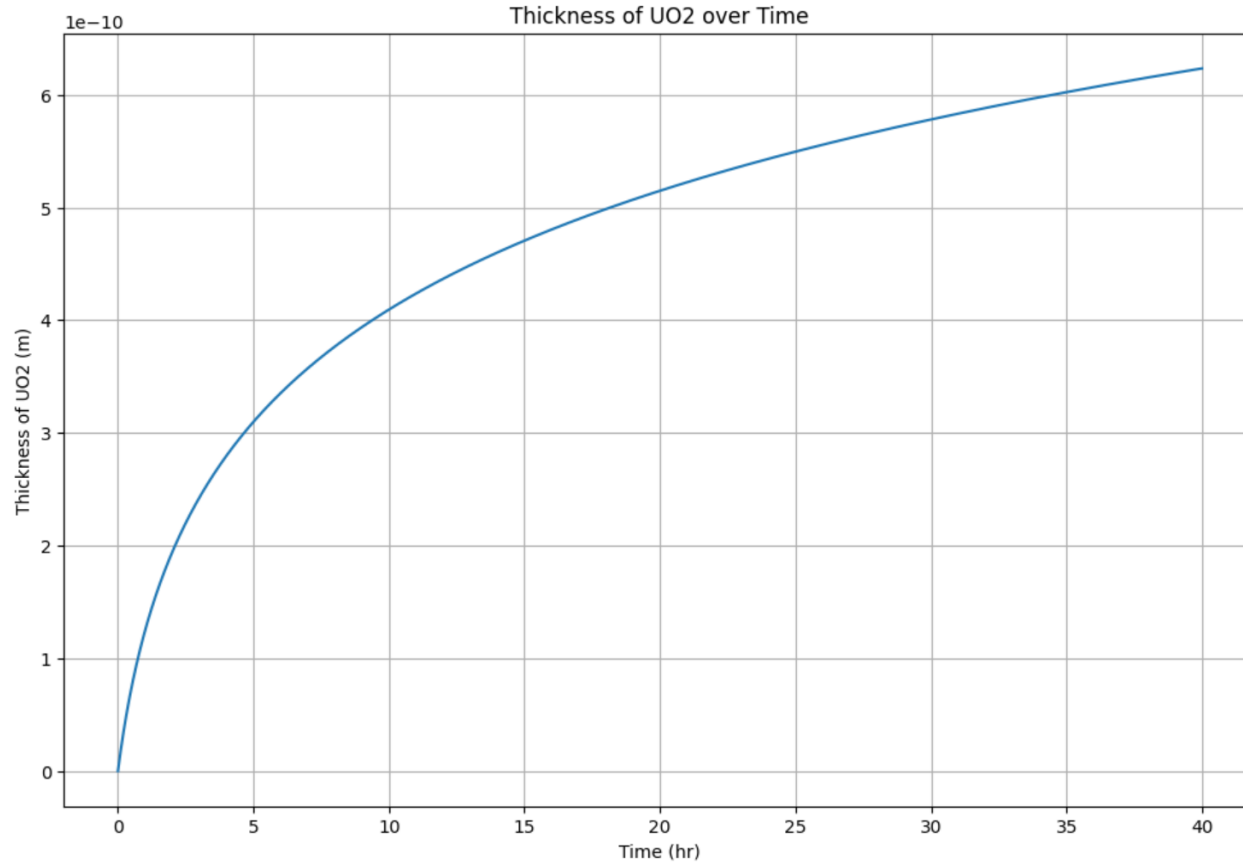
Mass transport rate at 40 hours is $1.6053915428818343\text{e-}11$ mol/s



with an average diffusion coefficient $D = 9 \text{ cm}^2/\text{sec}$ by eq. (11) and a pressure gradient determined by eq. (12) to be 5.4×10^{-7} atm yielded a mass transport value 1.6×10^{-11} moles UO_2/sec . The agreement between

GROWTH OF URANIUM DIOXIDE
SINGLE CRYSTALS BY CHEMICAL
VAPOR DEPOSITION* R. N. SINGH
and R. L. COBLE

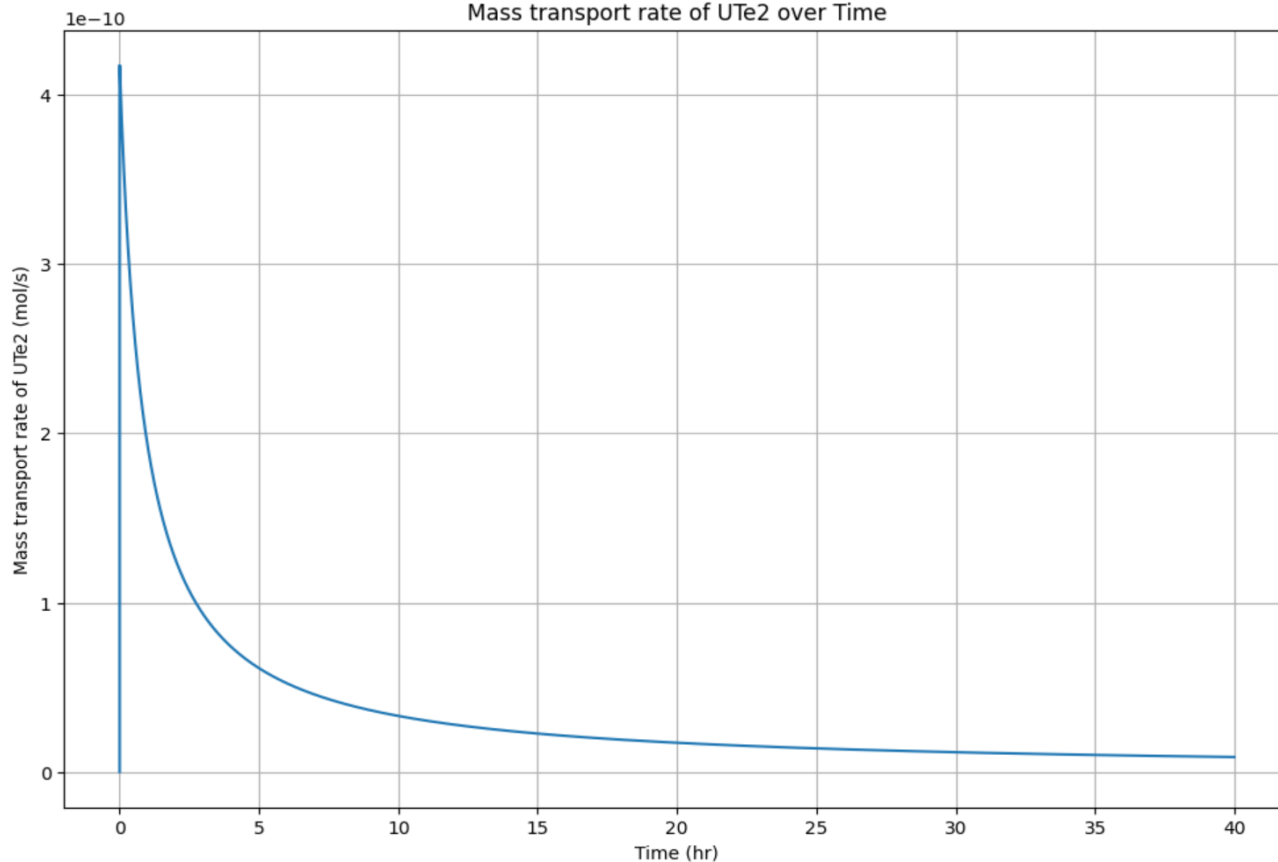
Predicting the thickness of UO₂ on the substrate over time



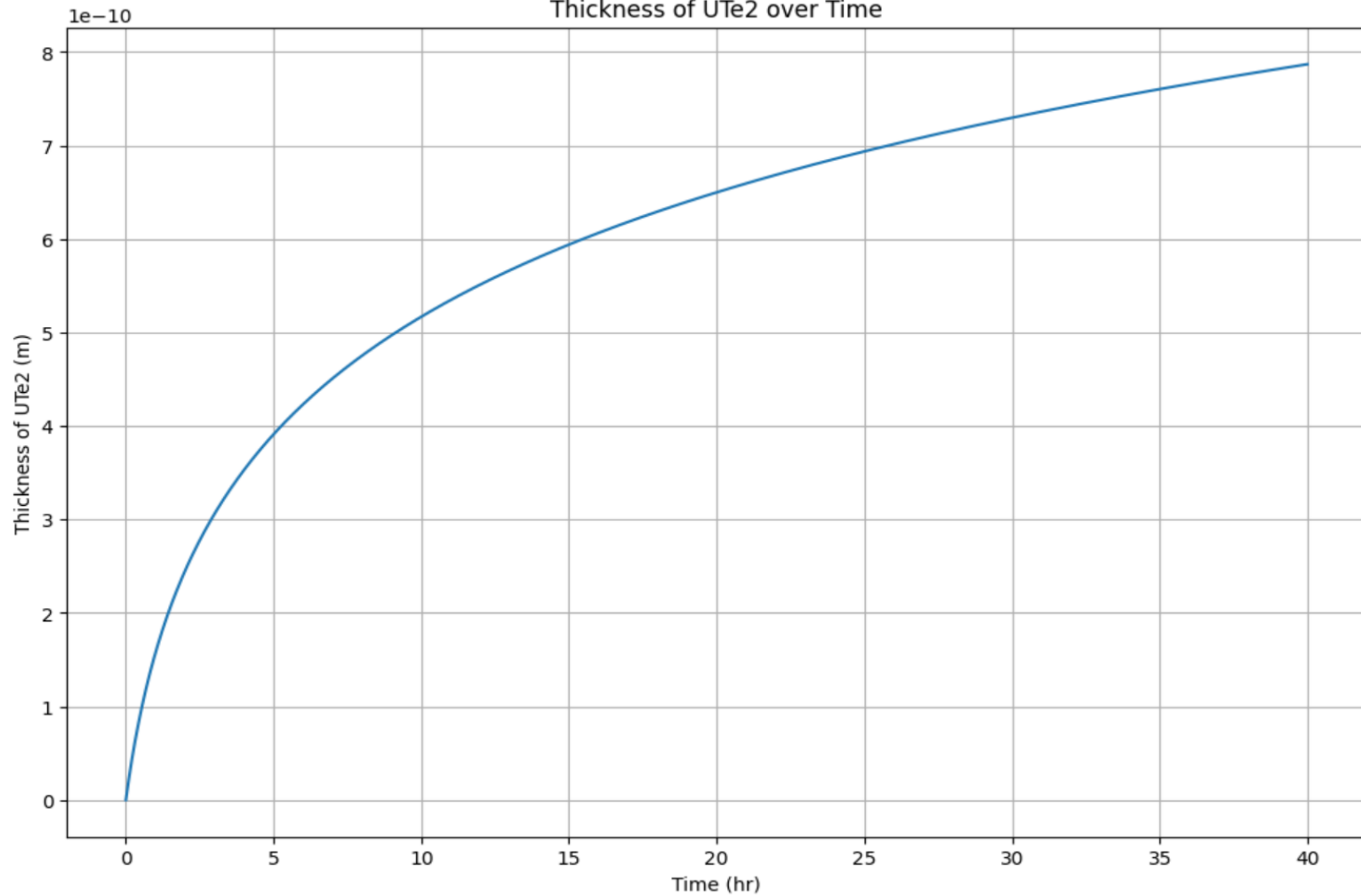
Mass transport rate (mol/s) vs Time (hr) UTe_2

Mass transport rate at 40 hours is $8.789081733154545e-12$ mol/s

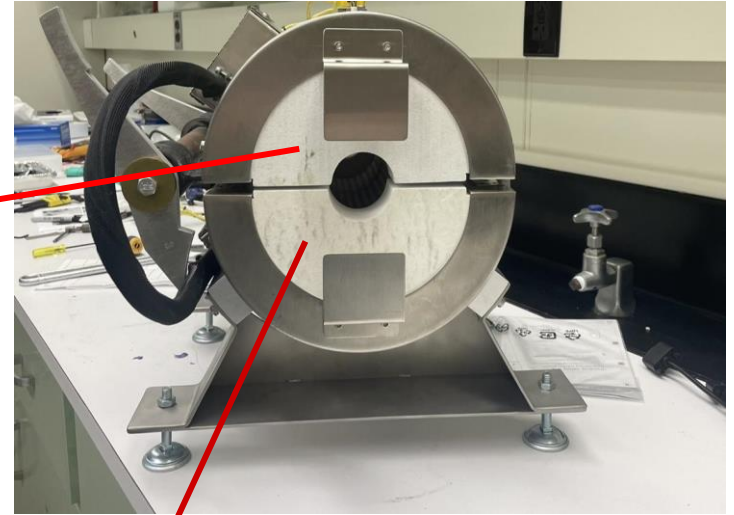
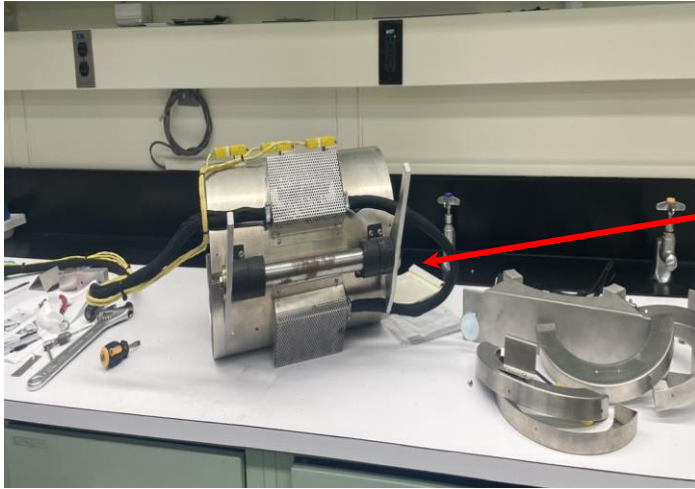
$8.8e-12$ mol/s



Thickness of UTe2 over Time

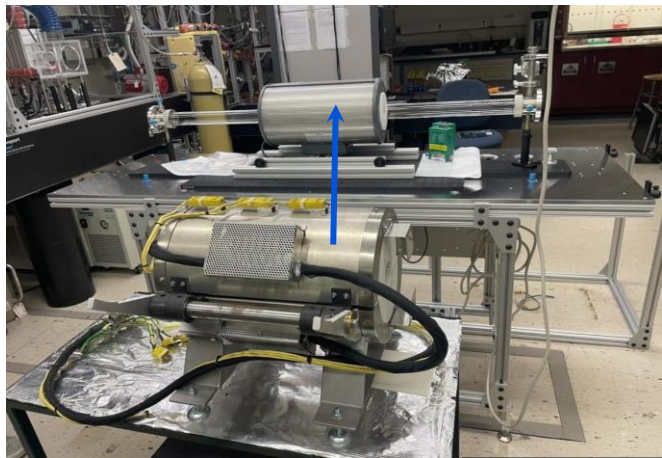


Experimental Setup



Changed high
temperature
thermal insulator

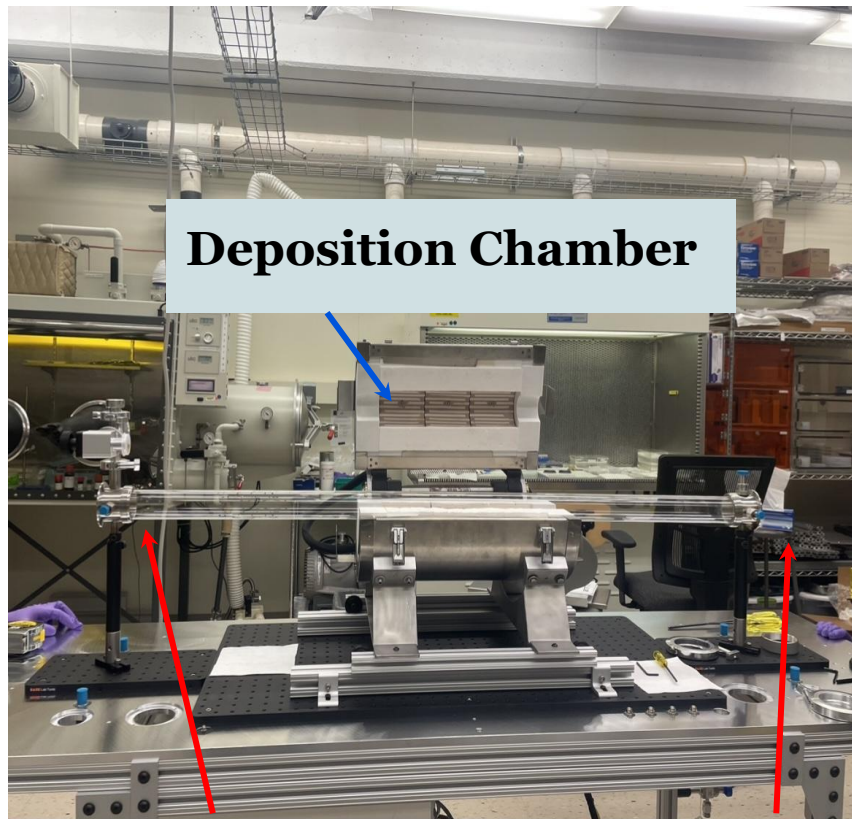
Experimental Setup Continued



Replaced



**Plastic Cage ->
Safety**



Deposition Chamber

Exhaust Side

In Take Side

Next Steps

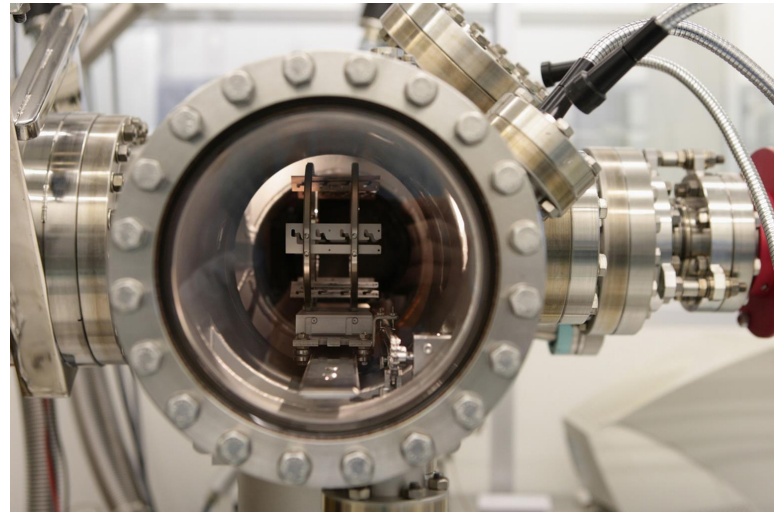
- Standard Operating Procedure
- Advancing the Software
- Completing the set up
- Testing
- Growing UTe_2 thin films



<https://angstromengineering.com/tech/chemical-vapor-deposition/>

Let's Summarize!

- Chemical Vapor Deposition of UTe₂
 - Software Simulation
 - Experimental Setup
- Future Work



Thin Films Deposition

<https://www.micronit.com/manufacturing/capabilities/thin-film-deposition>

Acknowledgements

Butch Lab:

Nicholas Butch, Corey Frank, Thomas Halloran, Peter Czajka, Sylvia Lewin, Gicela Saucedo, Patrick Chen, Rayan Daroowalla, Elan Moskowitz, Maximilian Shen

NCNR:

Susana Marujo Teixeira, Julie Borchers, Leland Harriger

MML

SURF:

SURF Directors, SURF Program Director Cara O'Malley

CHRNS